

	Hits	Search Text	DBs
26	0	((substrate or wafer or device or workpiece) same (support\$3 or stage or hold\$3 or pedestal) same (resist or photoresist or photocur\$4) same (irradiat\$4 or illuminat\$4 or (UV near9 source) or excimer or KrF or ArF or e\$3beam or (electron near4 beam) or EUV or DUV or VUV or laser)) and pattern\$3 and (((pattern\$6 near5 device) or mask\$4 or reticle) same (\$4lithograph\$6 or photolithograph\$6) same (laser or irradiat\$4 or (ion near9 beam)) same ((organic near9 compound) or fluoroalkanes or alkane or hydrocarbon) same ((nitrogen or N\$2) near12 (oxygen or oxide)))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
27	0	((((pattern\$6 near5 device) or mask\$4 or reticle) same (project\$4) same (\$4lithograph\$6 or photolithograph\$6) same (laser or irradiat\$4 or (ion near9 beam)) same ((organic near9 compound) or fluoroalkanes or alkane or hydrocarbon) same ((nitrogen or N\$2) near12 (oxygen or oxide)))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
28	3	((((pattern\$6 near5 device) or mask\$4 or reticle) same (\$4lithograph\$6 or photolithograph\$6) same (laser or irradiat\$4 or (ion near9 beam)) same ((organic near9 compound) or fluoroalkanes or alkane or hydrocarbon or methane or ethane or methyl or ethyl or alkyl) same ((nitrogen or N\$2) near12 (oxygen or oxide)))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
29	39	((pattern\$6 near5 device) or mask\$4 or reticle) same (\$4lithograph\$6 or photolithograph\$6) same (laser or irradiat\$4 or (ion near9 beam)) same ((organic near9 compound) or fluoroalkanes or alkane or hydrocarbon or methane or ethane or methyl or ethyl or alkyl or fluoromethane) same ((nitr\$4 near6 (oxygen or oxide)) or NO\$3))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
30	5	((pattern\$6 near5 device) or mask\$4 or reticle) same (\$4lithograph\$6 or photolithograph\$6) same (laser or irradiat\$4 or (ion near9 beam)) same ((organic near9 compound) or fluoroalkanes or alkane or hydrocarbon or methane or ethane or methyl or ethyl or (halogen\$4 near9 alkane\$3) or alkyl or fluoromethane or CF\$4) same ((nitr\$4 near6 (oxygen or oxide))))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
31	72	(projection near9 (optical or \$5lithograph\$4) near9 (system or apparatus)) and ((radiation or light or optical or laser or project\$4 or \$4lithograph\$6) same (source or system or apparatus)) and ((substrate or wafer or device or workpiece) same (support\$3 or stage or hold\$3)) and pattern\$4 and ((plasma or e\$3beam or (electron near4 beam) or beam or RF or (electro\$3magnetic near6 field) or (plasma near5 source) or EUV or DUV)) and ((pattern\$6 near5 device) or mask\$4 or reticle or photo\$4mask) and (gas\$3 same (plasma or ion\$3beam or beam or laser or ion\$4assist\$5) same (((nitrogen or nitrous or nitric) near16 (oxide or dioxide)) or "NO.sub.2"))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
32	72	S31 NOT S29	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB